

B2 4. (Amended) The composition according to claim 2, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol[,] and propylene glycol.

B3 25. (Amended) The composition according to claim 23, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol[,] and propylene glycol.

sub C3 82. (Amended) A composition for selectively etching a doped substance, said composition consisting essentially of:

a non-aqueous composition of isopropanol and at least two inorganic acids[, wherein a major component of said composition is non-aqueous].

83. (Amended) A composition for selectively etching a doped substance, said composition consisting essentially of:

B4 a non-aqueous composition of propylene glycol and at least two inorganic acids[, wherein a major component of said composition is non-aqueous].

84. (Amended) A composition for selectively etching a doped amorphous, doped pseudo-crystalline or doped polycrystalline silicon, said composition consisting essentially of:

a non-aqueous composition of an alcohol and at least two inorganic acids[, wherein a major component of said composition is non-aqueous].

85. (Amended) A composition for selectively etching doped germanium, said composition consisting essentially of:

a non-aqueous composition of an alcohol and at least two inorganic acids[, wherein a major component of said composition is non-aqueous].

86. (Amended) A composition for selectively etching gallium arsenide, said composition consisting essentially of: